

CBC SEMINAR ANNOUNCEMENT



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Sketch and Peel Lithography for Multiscale Patterning

Reliable multiscale patterning across nanometer to millimeter scale is of great importance but challenging for various applications. In this presentation, I will first share a unique multiscale patterning process called “sketch and peel” lithography. The process is based on electron or ion-beam lithography, but it allows much higher patterning throughput with enhanced resolution for multiscale features compared to conventional processes. The applications of this unique process for transfer printing and flexible & stretchable devices will also be summarized. During the talk, a brief introduction to our work on other extreme micro/nanomanufacturing approaches and relevant applications will also be given.

Date: 16 August 2019 (Friday)
Time: 2.00pm – 3.30pm
Venue: Level 3, MAS Executive Classroom 1
Host: Associate Professor Ling Xing Yi